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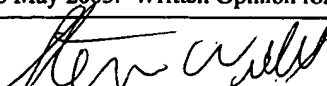
OCT 09 2003

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SHEET 1 OF 1

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 005199 USA/Consilium/Consilium		SERIAL NO. 09/725,908 RECEIVED OCT 10 2003	
				APPLICANT Yueshian T. CHI et al.		Technology Center 2100	
				FILING DATE November 30, 2000		GROUP 2152	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
<i>W</i>	5,901,313	05/04/99	Wolf et al.			09/02/97	
<i>W</i>	6,002,989	12/14/99	Shiba et al.			04/01/97	
<i>W</i>	6,094,688	07/25/00	Mellen-Garnett et al.			03/12/98	
<i>W</i>	6,340,602	01/22/02	Johnson et al.			02/12/01	
<i>W</i>	6,345,288	02/05/02	Reed et al.			05/15/00	
<i>W</i>	6,368,879	04/09/02	Toprac			09/22/99	
<i>W</i>	US-2002/0107604	08/08/02	Riley et al.			12/06/00	
<i>W</i>	6,470,230	10/22/02	Toprac et al.			01/04/00	
<i>W</i>	6,482,660	11/19/02	Conchieri et al.			03/19/01	
<i>W</i>	6,567,717	05/20/03	Krivokapic et al.			01/19/00	
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
<i>W</i>	WO 99/59200	11/18/99	WIPO			X	
<i>W</i>	WO 01/52319	07/19/01	WIPO			X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>W</i>	Williams, Randy, Dadi Gudmundsson, Kevin Monahan, Raman Nurani, Meryl Stoller and J. George Shanthikumar. October 1999. "Optimized Sample Planning for Wafer Defect Inspection," <i>Semiconductor Manufacturing Conference Proceedings, 1999 IEEE International Symposium on Santa Clara, CA</i> . Piscataway, NJ. pp. 43 - 46.						
<i>W</i>	23 July 2003. Invitation to Pay Additional Fees and Communication Relating to the Results of the Partial International Search for PCT/US02/19116.						
<i>W</i>	01 August 2003. Written Opinion for PCT/US01/27406.						
<i>W</i>	20 August 2003. Written Opinion for PCT/US01/22833.						
EXAMINER <i>W</i>			DATE CONSIDERED <i>9/14/00</i>				

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
✓	3,767,900	10/23/73	Chao et al.			06/23/71	
✓	3,920,965	11/18/75	Sohrwardy			03/04/74	
✓	4,368,510	01/11/83	Anderson			10/20/80	
✓	4,616,308	10/07/86	Morshedi et al.			12/02/85	
✓	4,663,703	05/05/87	Axelby et al.			10/02/85	
✓	5,347,446	09/13/94	Iino et al.			02/10/92	
✓	5,519,605	05/21/96	Cawlfeld			10/24/94	
✓	6,128,016	10/03/00	Coelho et al.			12/20/96	
✓	6,219,711	04/17/01	Chari			10/01/97	
✓	6,249,712	06/19/01	Boiquaye			09/25/96	
✓	6,278,899	08/21/01	Piche et al.			10/06/98	
✓	2001/0039462	11/08/01	Mendez et al.			04/02/01	
✓	2001/0040997	11/15/01	Tsap et al.			05/15/01	
✓	2002/0128805	09/12/02	Goldman et al.			12/26/00	
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
✓	EP 1 067 757	01/10/01	Europe			X	
✓	WO 01/33277	05/10/01	WO			X	
✓	WO 02/31613 A2	04/18/02	WO			X	
✓	WO 02/31613 A3	04/18/02	WO			X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
✓	Levine, Martin D. 1985. <i>Vision in Man and Machine</i> . New York: McGraw-Hill, Inc. pp. ix-xii, 1-58.						
✓	Pilu, Maurizio. September 2001. "Undoing Page Curl Distortion Using Applicable Surfaces." <i>IEEE International Conference on Image Processing</i> . Thessalonica, Greece.						
✓	23 May 2003. Written Opinion for PCT/US01/24910.						
EXAMINER				DATE CONSIDERED			
				16/3/06			

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